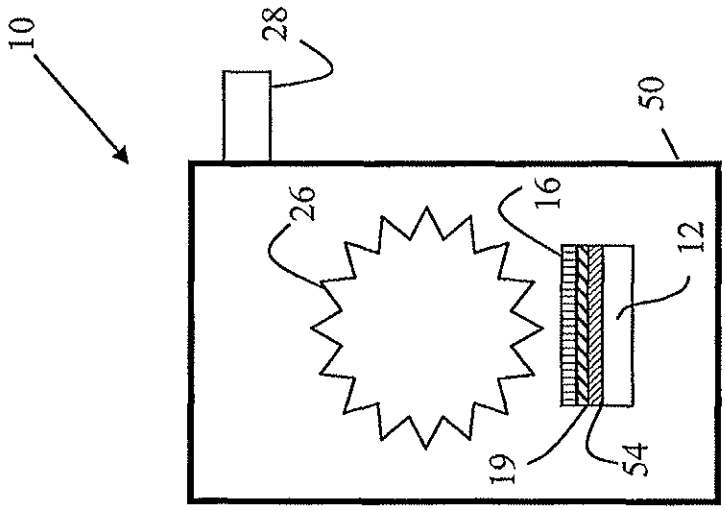


FIGURE 1

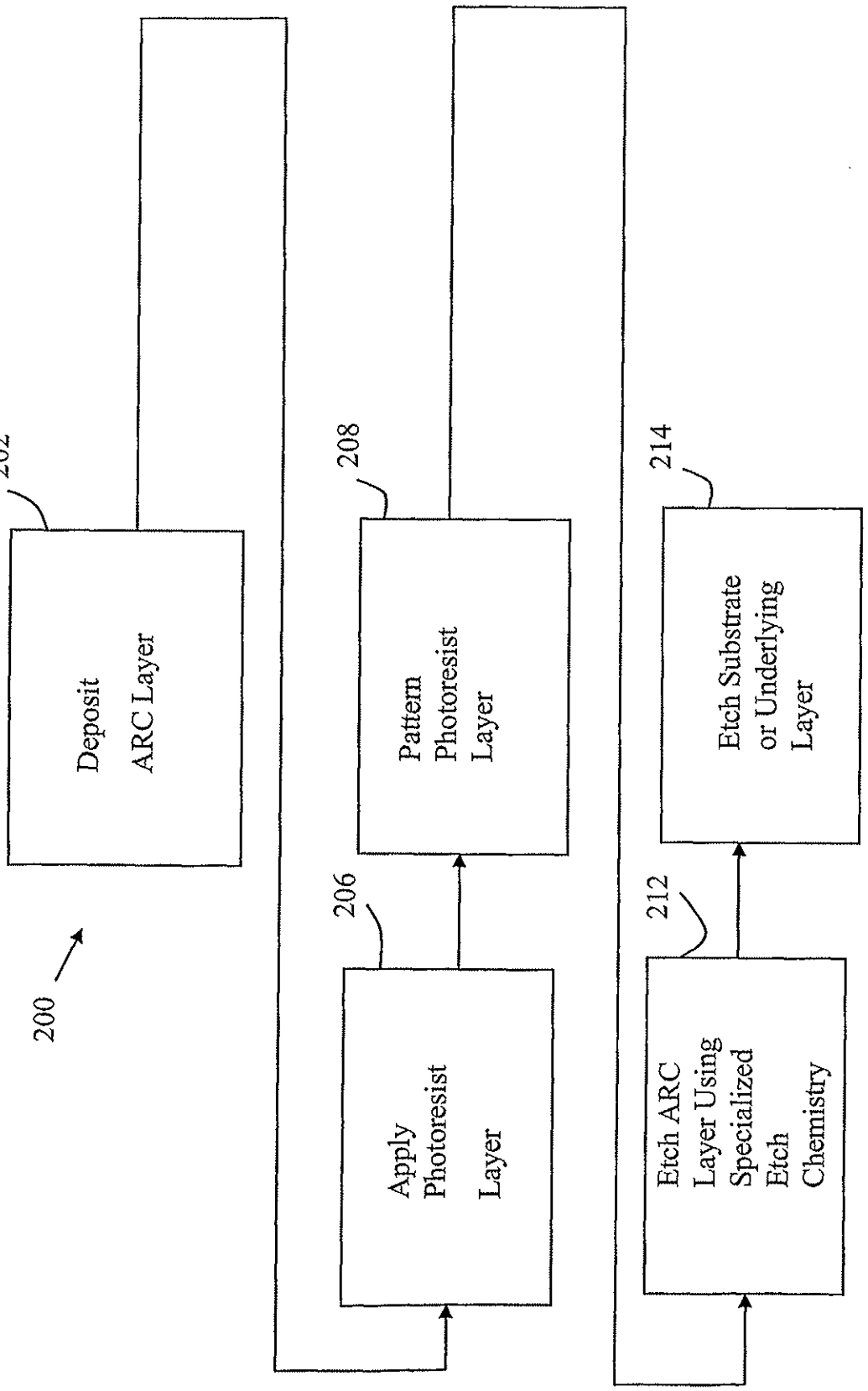

200
202
Deposit ARC Layer
206
Apply Photoresist Layer
208
Pattern Photoresist Layer
212
Etch ARC Layer Using Specialized Etch Chemistry
214
Etch Substrate or Underlying Layer

Figure 2

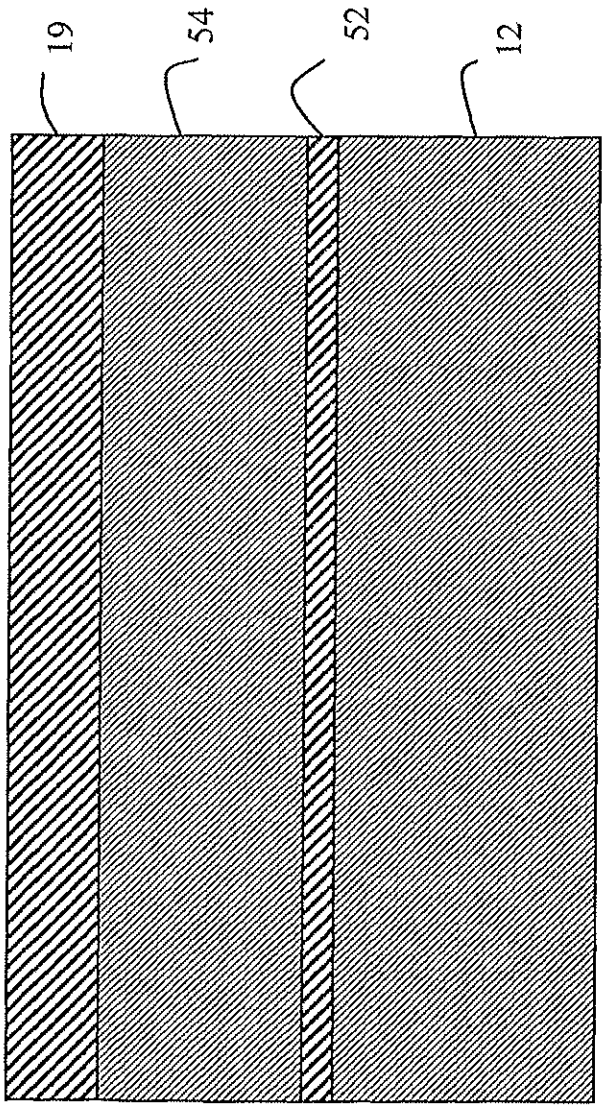


Figure 3

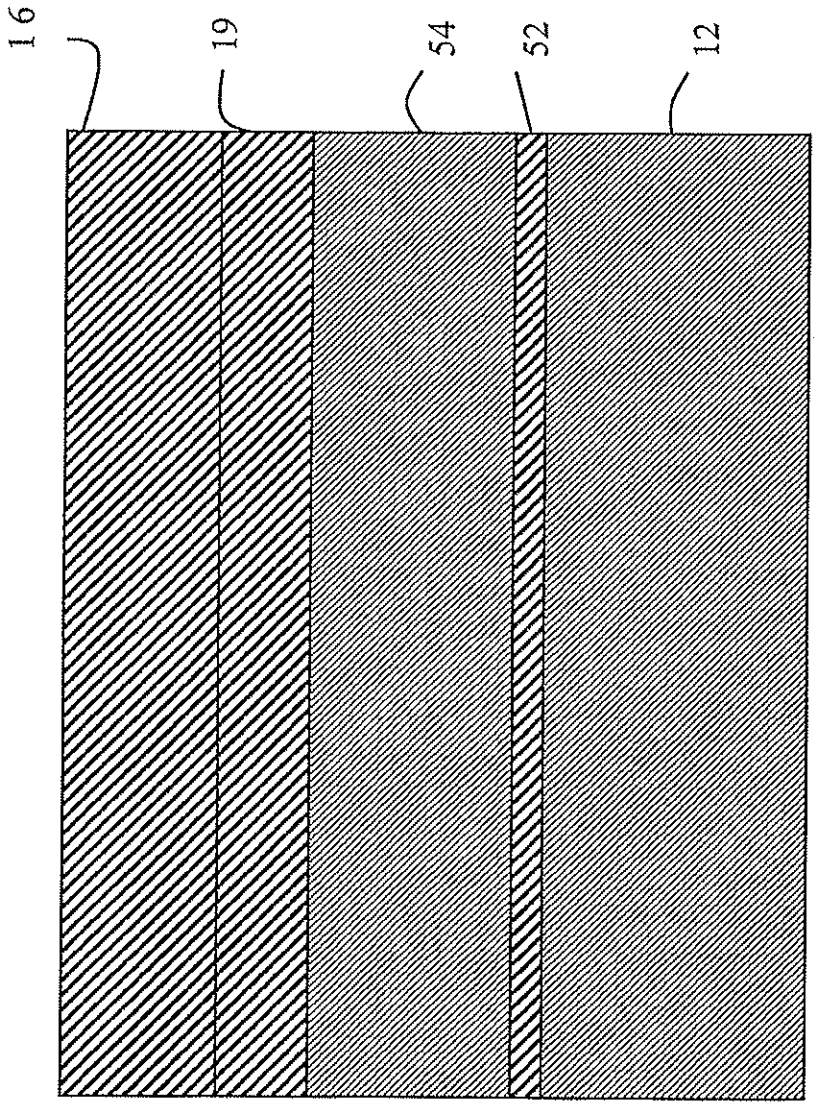


Figure 4

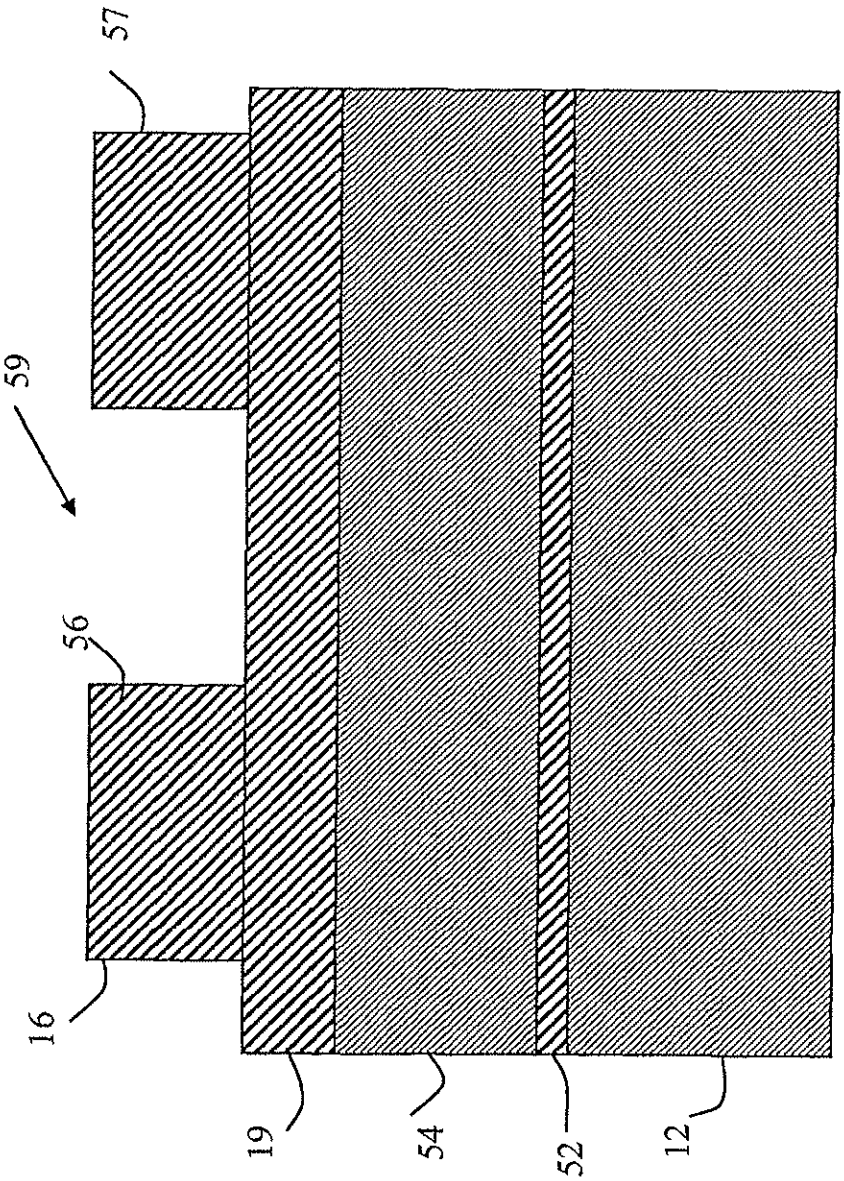


Figure 5

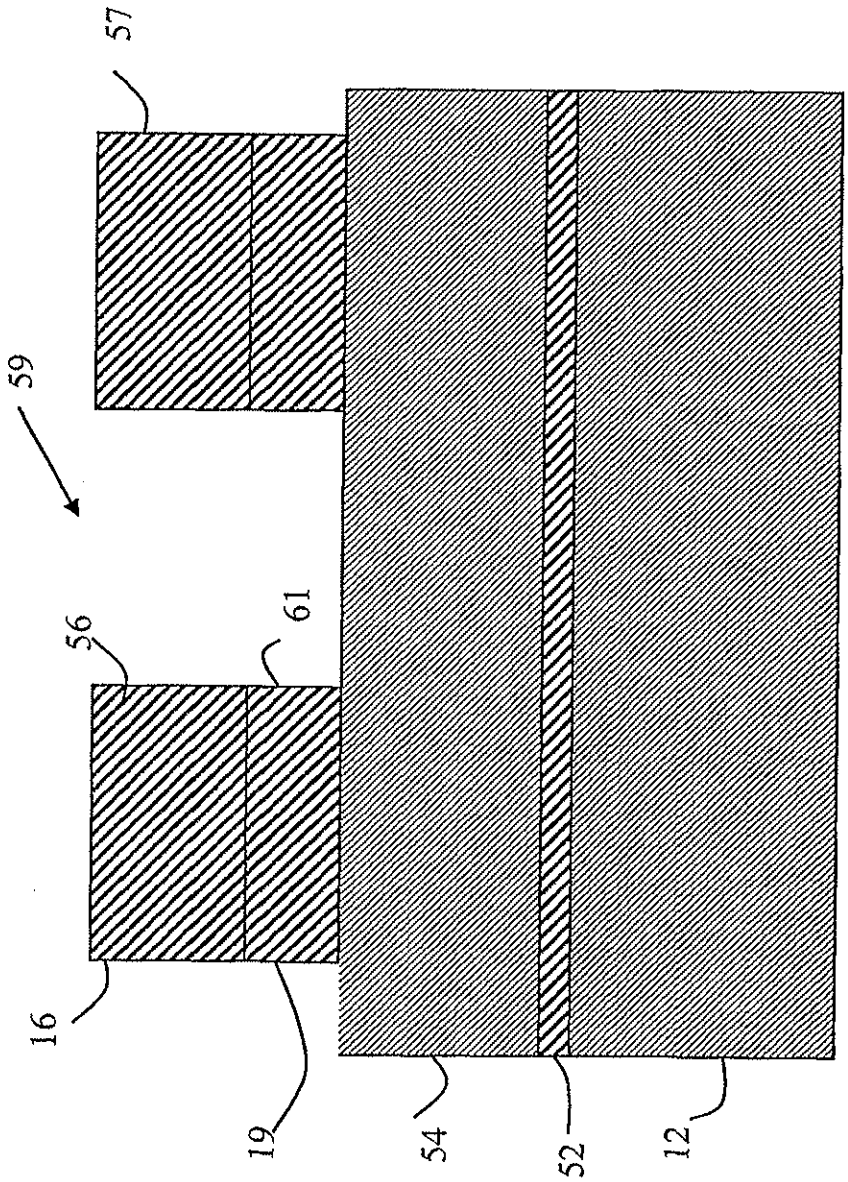


Figure 6

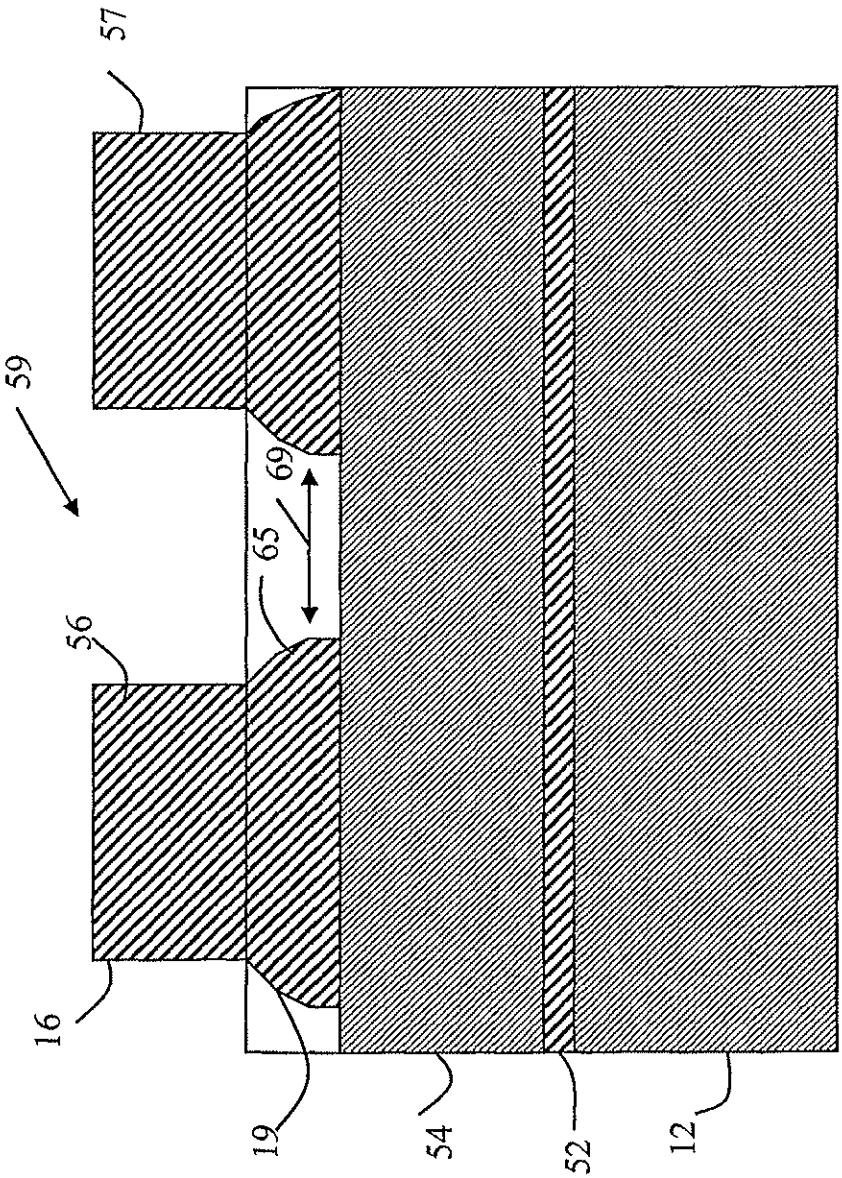


Figure 7

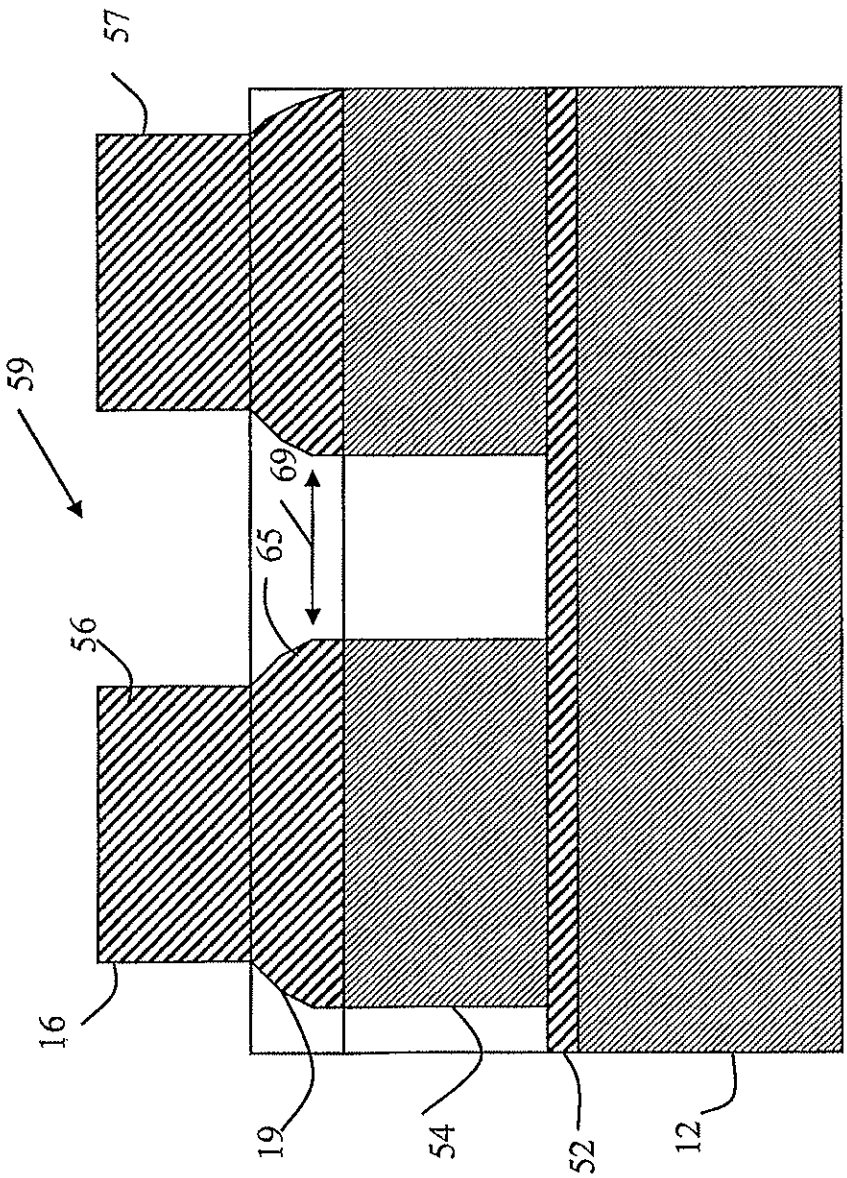


Figure 8

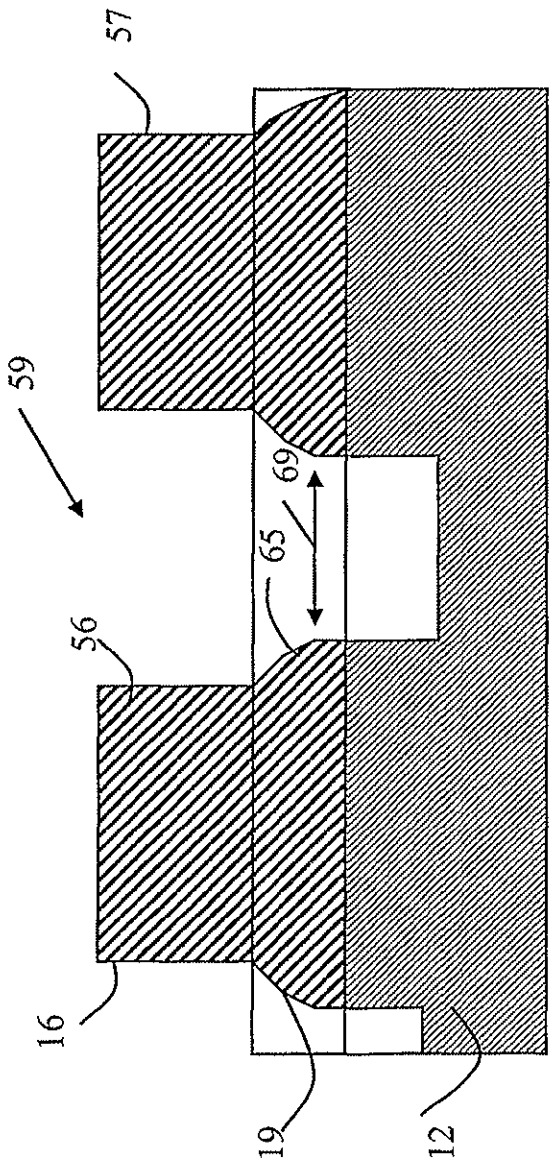


Figure 9

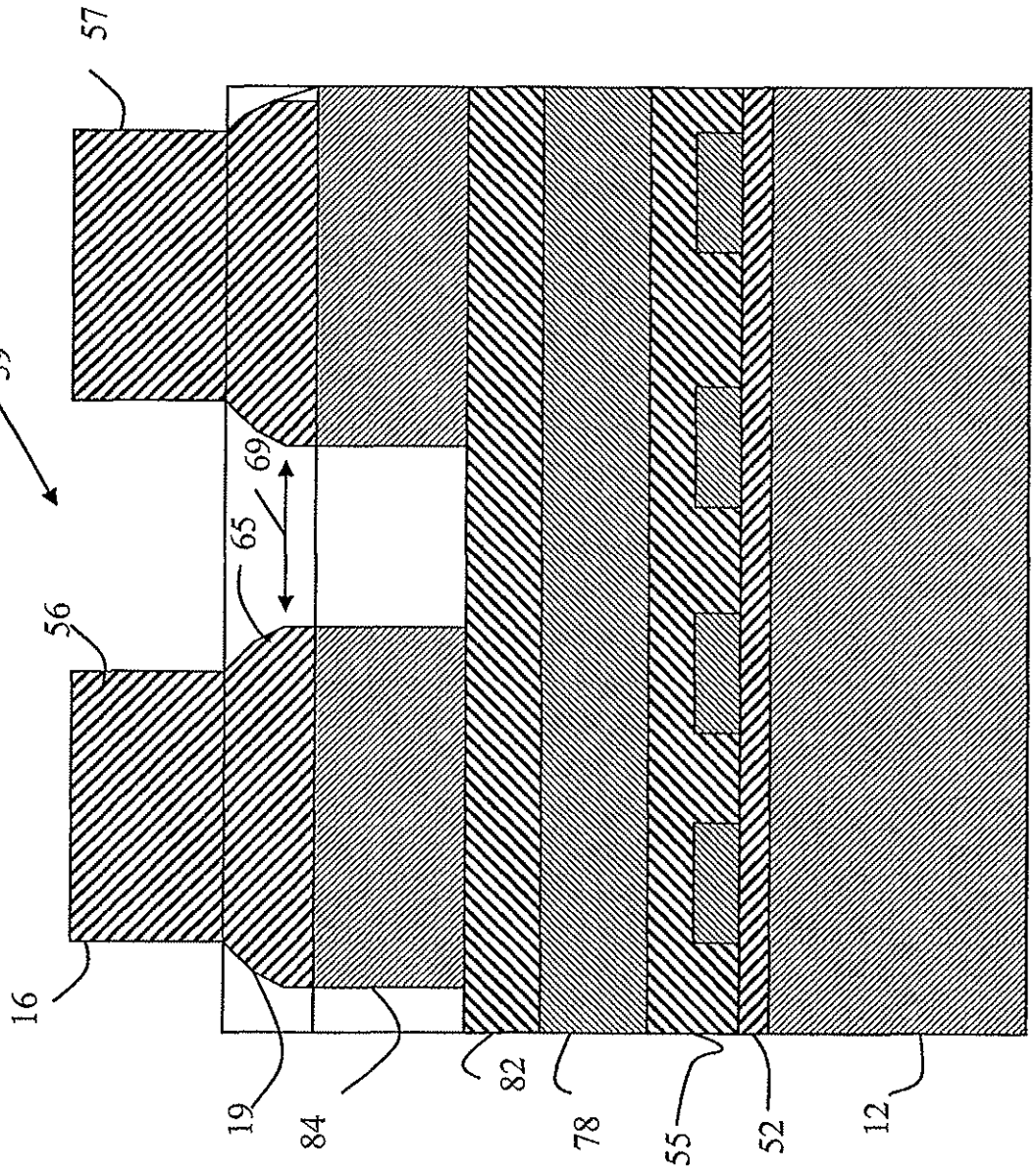


Figure 10